

Supporting Information

Synthesis and FET characteristics of phenylene-vinylene and anthracene-vinylene compounds containing cyano groups

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1. Differential pulse voltammograms

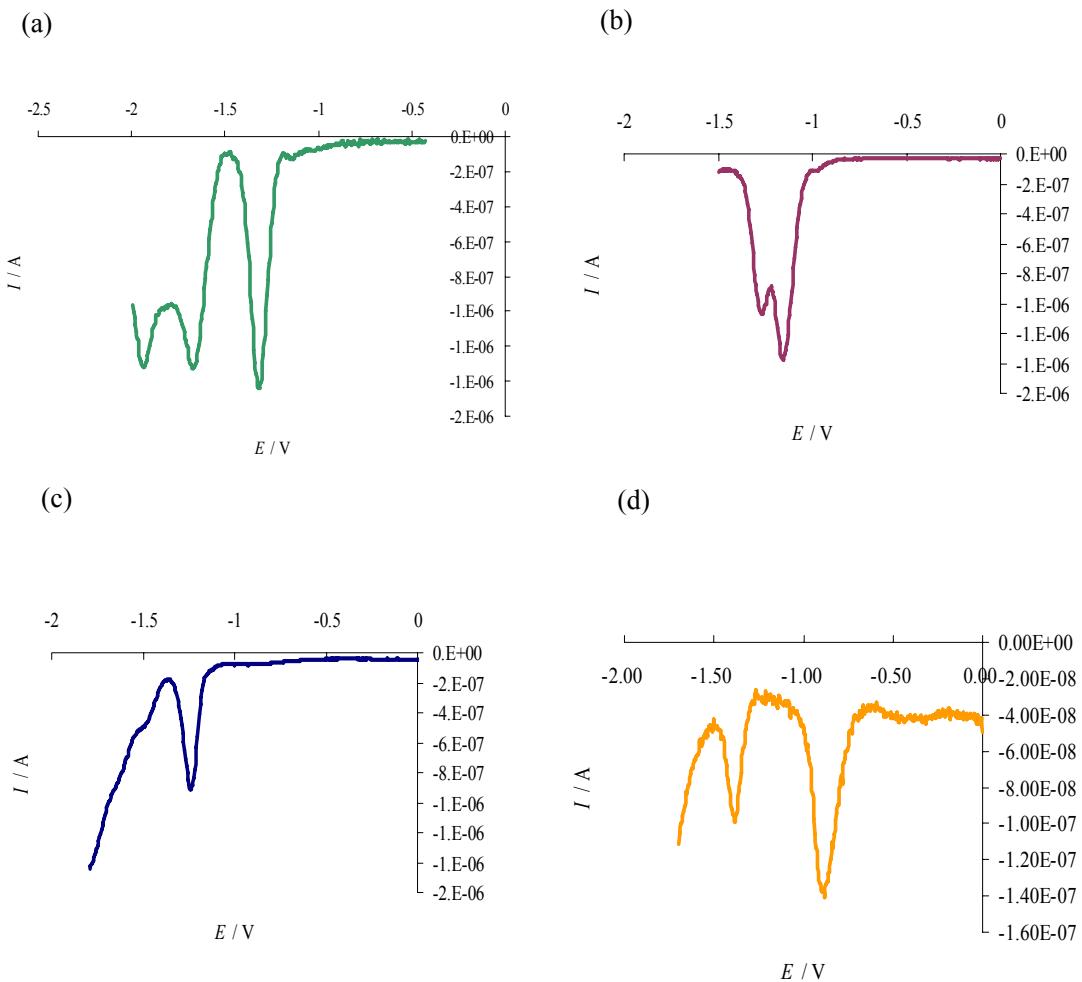


Figure S1. Differential pulse voltammograms of **1** (a), **2a** (b), **3a** (c) and **4** (d) in CH_2Cl_2 .
0.1 M n -Bu₄NPF₆, Pt electrode, scan rate 100 mV s⁻¹, V vs SCE.

2. DFT calculations

B3LYP/6-31G(d) level using the Gaussian program

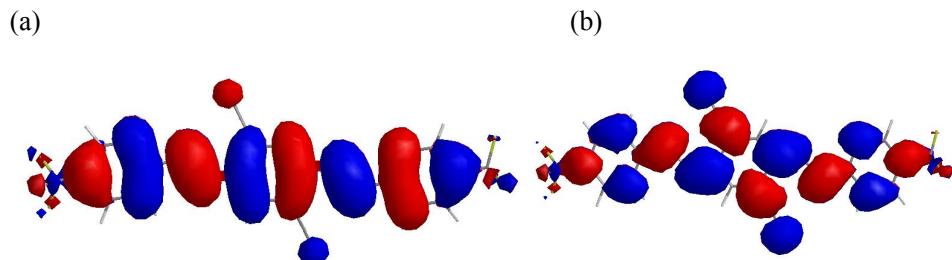


Figure S2. (a) HOMO orbital (6.42 eV) and (b) LUMO orbital (3.27 eV) of **1**.

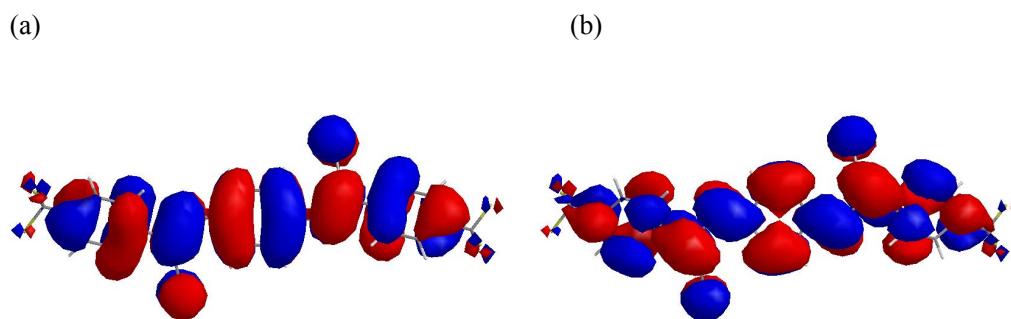


Figure S3. (a) HOMO orbital (6.34 eV) and (b) LUMO orbital (3.22 eV) of **2a**.

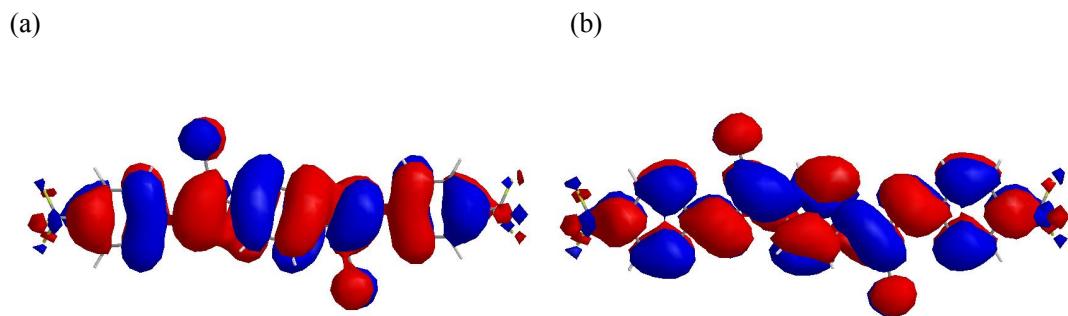


Figure S4. (a) HOMO orbital (6.53 eV) and (b) LUMO orbital (3.12 eV) of **3a**.

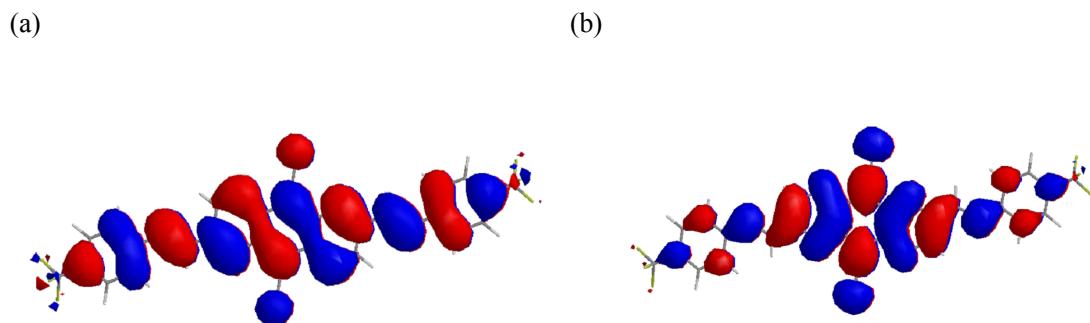
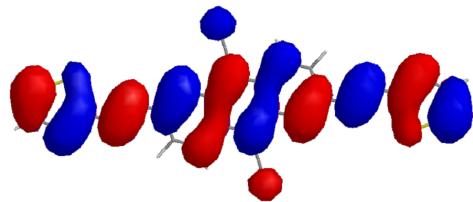


Figure S5. (a) HOMO orbital (6.07 eV) and (b) LUMO orbital (3.41 eV) of **4**.

(a)



(b)

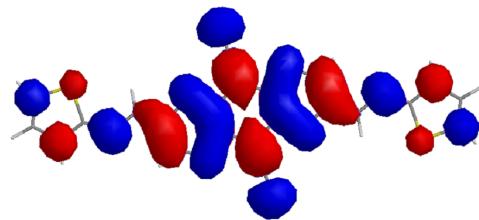
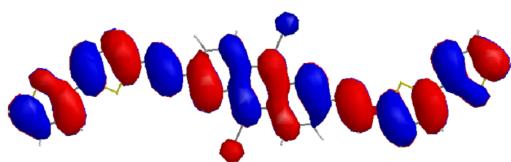


Figure S6. (a) HOMO orbital (5.50 eV) and (b) LUMO orbital (3.05 eV) of **5**.

(a)



(b)

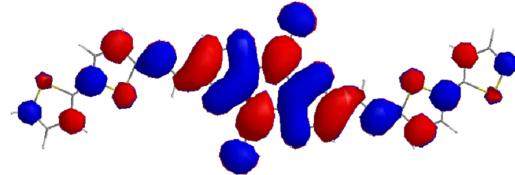


Figure S7. (a) HOMO orbital (5.24 eV) and (b) LUMO orbital (3.08 eV) of **6**.

3. FET characteristics

3-1. Bottom-contact devices

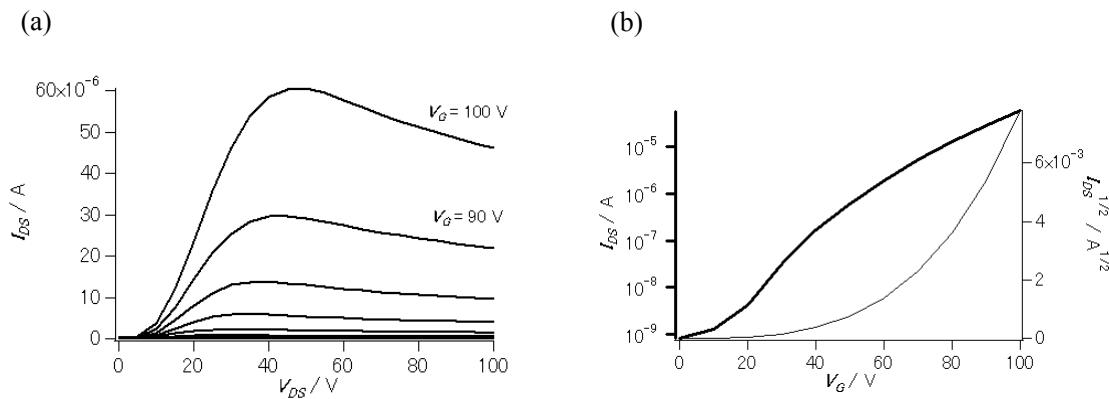


Figure S8. (a) Output characteristics of **1** and (b) transfer characteristics of **1** at a drain voltage of 50 V ($T_{\text{sub}} = 50^\circ\text{C}$, HMDS). The mobility calculated in the saturation regime is $6.6 \times 10^{-4} \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$ (SiO_2 : 300 nm, active layer: 50 nm, $L/W = 25 \mu\text{m}/294000 \mu\text{m}$).

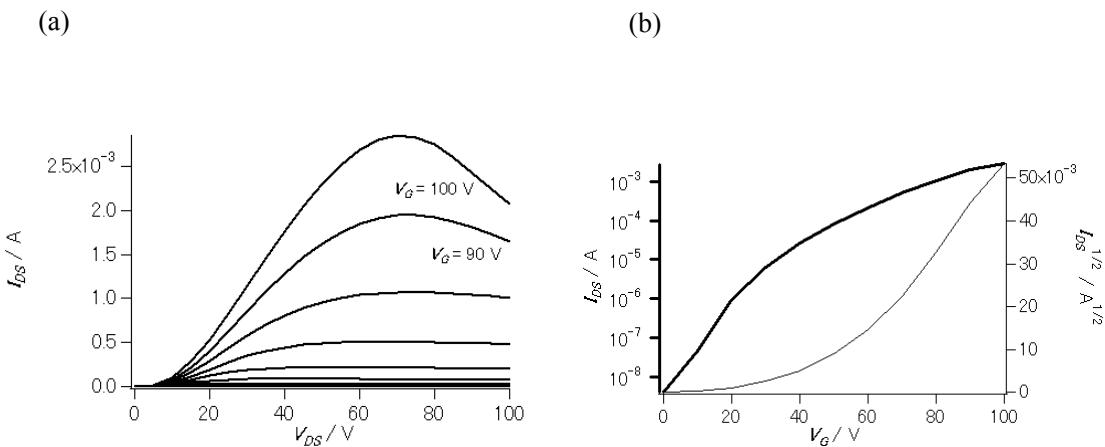


Figure S9. (a) Output characteristics of **2a** and (b) transfer characteristics of **2a** at a drain voltage of 70 V ($T_{\text{sub}} = 50^\circ\text{C}$, Bare). The mobility calculated in the saturation regime is $1.6 \times 10^{-2} \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$ (SiO_2 : 300 nm, active layer: 50 nm, $L/W = 25/294000$).

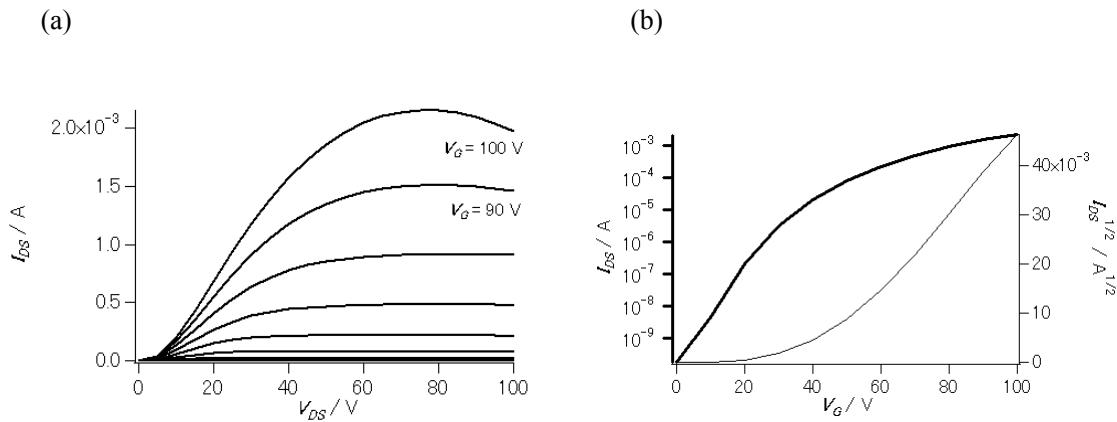


Figure S10. (a) Output characteristics of **2b** and (b) transfer characteristics of **2b** at a drain voltage of 75 V ($T_{\text{sub}} = 20^\circ\text{C}$, Bare). The mobility calculated in the saturation regime is $1.1 \times 10^{-2} \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$ (SiO₂: 300 nm, active layer: 50 nm, $L/W = 25/294000$).

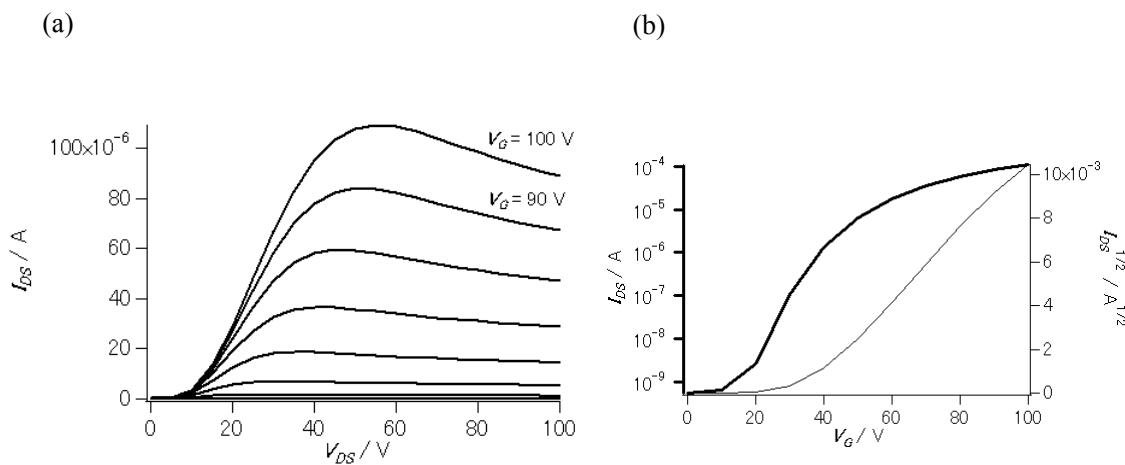


Figure S11. (a) Output characteristics of **3a** and (b) transfer characteristics of **3a** at a drain voltage of 55 V ($T_{\text{sub}} = 20^\circ\text{C}$, Bare). The mobility calculated in the saturation regime is $4.5 \times 10^{-4} \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$ (SiO₂: 300 nm, active layer: 50 nm, $L/W = 25/294000$).

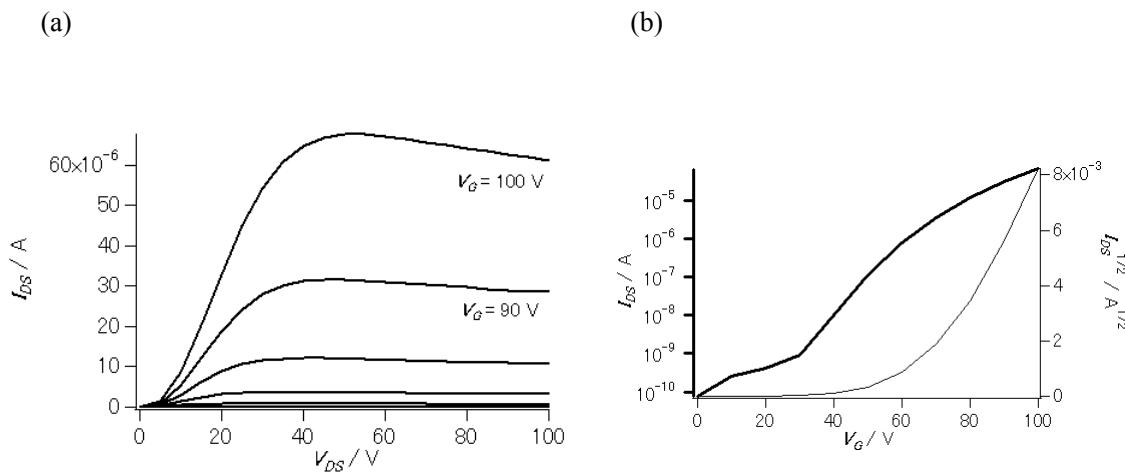


Figure S12. (a) Output characteristics of **3b** and (b) transfer characteristics of **3b** at a drain voltage of 50 V ($T_{\text{sub}} = 50 \text{ }^{\circ}\text{C}$, HMDS). The mobility calculated in the saturation regime is $9.2 \times 10^{-4} \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$ (SiO₂: 300 nm, active layer: 50 nm, $L/W = 25/294000$).

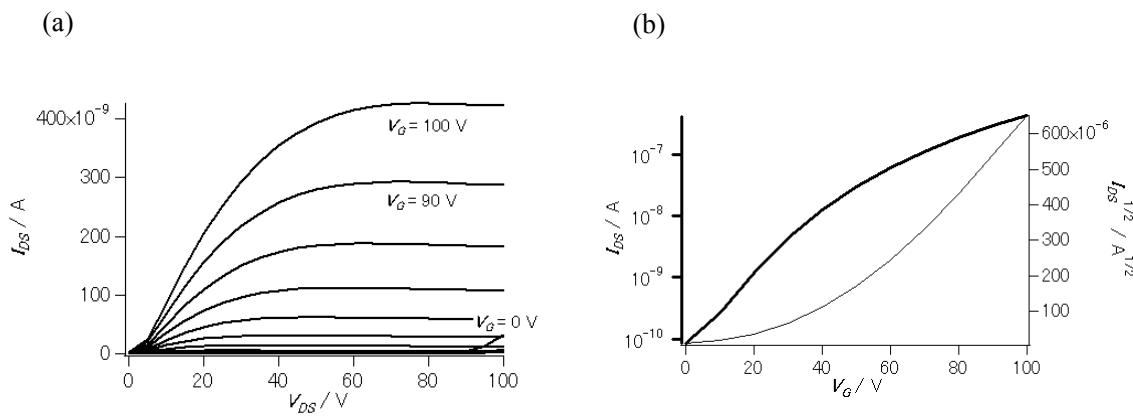


Figure S13. (a) n-Type output characteristics of **5** and (b) transfer characteristics of **5** at a drain voltage of 70 V ($T_{\text{sub}} = 20 \text{ }^{\circ}\text{C}$, HMDS). The mobility calculated in the saturation regime is $1.8 \times 10^{-6} \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$ (SiO₂: 300 nm, active layer: 50 nm, $L/W = 25/294000$).

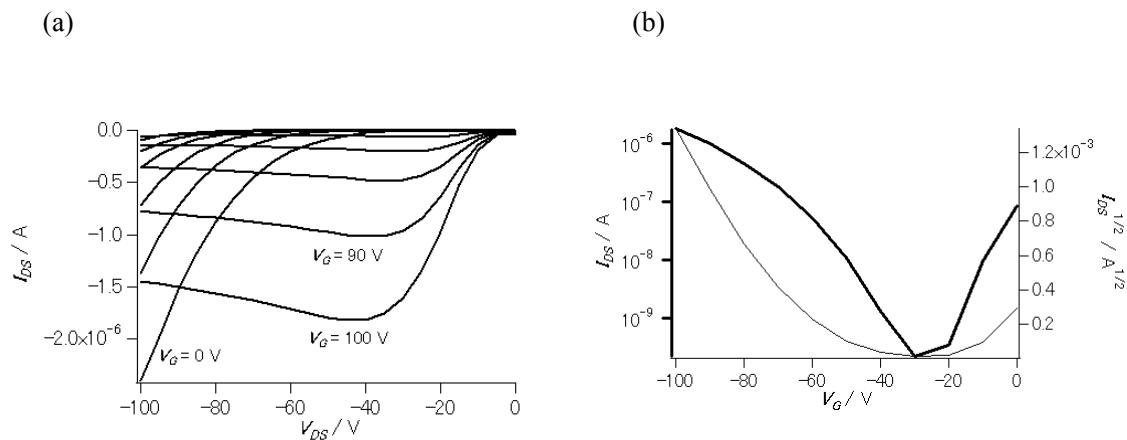


Figure S14. (a) p-Type output characteristics of **5** and (b) transfer characteristics of **5** at a drain voltage of 45 V ($T_{\text{sub}} = 20^\circ\text{C}$, HMDS). The mobility calculated in the saturation regime is $1.2 \times 10^{-6} \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$ (SiO_2 : 300 nm, active layer: 50 nm, $L/W = 25/294000$).

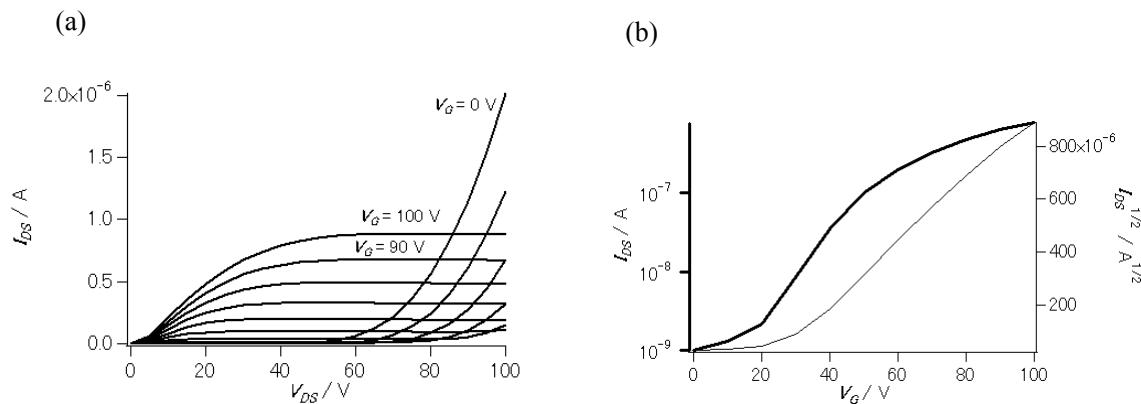


Figure S15. (a) n-Type output characteristics of **6** and (b) transfer characteristics of **6** at a drain voltage of 40 V ($T_{\text{sub}} = 20^\circ\text{C}$ HMDS). The mobility calculated in the saturation regime is $2.4 \times 10^{-6} \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$ (SiO_2 : 300 nm, active layer: 50 nm, $L/W = 25/294000$).

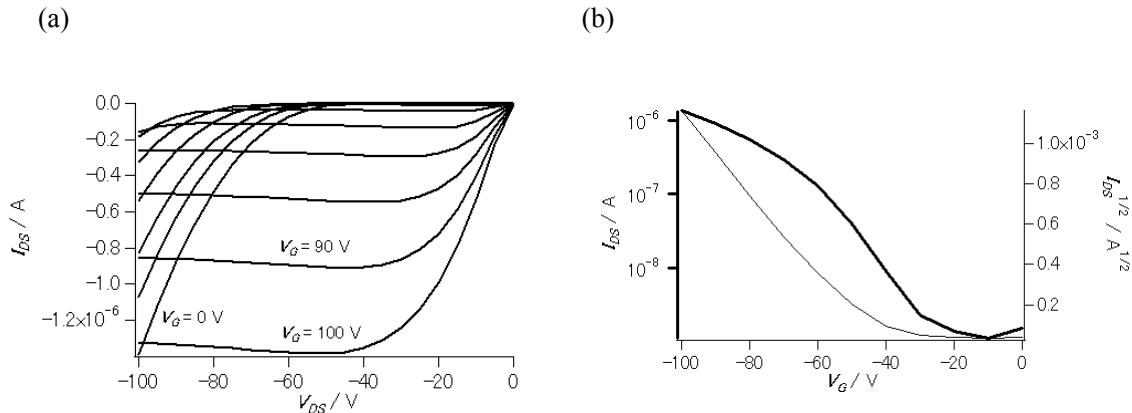


Figure S16. (a) p-Type output characteristics of **6** and (b) transfer characteristics of **6** at a drain voltage of 40 V ($T_{\text{sub}} = 20 \text{ }^{\circ}\text{C}$, HMDS). The mobility calculated in the saturation regime is $2.7 \times 10^{-6} \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$ (SiO_2 : 300 nm, active layer: 50 nm, $L/W = 25/294000$).

3-2. Top contact devices

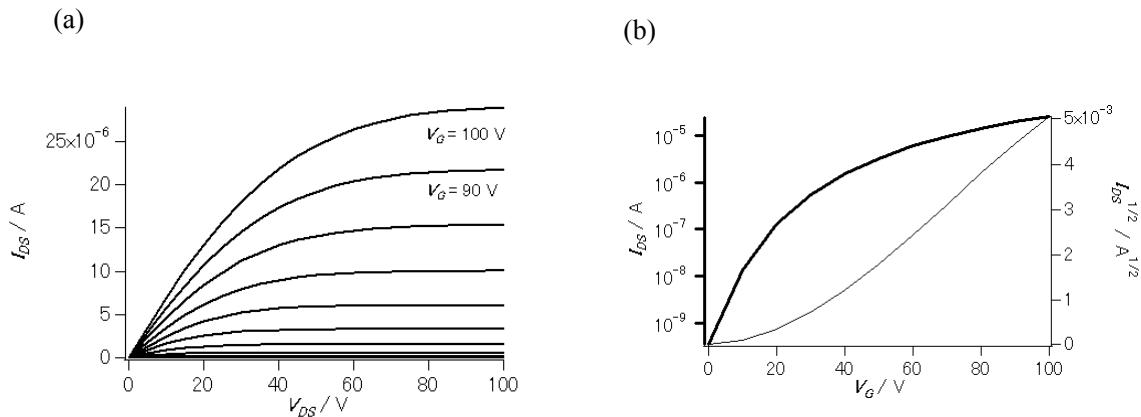


Figure S17. (a) Output characteristics of **2a** and (b) transfer characteristics of **2a** at a drain voltage of 55 V ($T_{\text{sub}} = 20 \text{ }^{\circ}\text{C}$, Bare). The mobility calculated in the saturation regime is $0.04 \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$ (SiO_2 : 200 nm, active layer: 30 nm, $L/W = 50/1000$).

3-3. Solution process

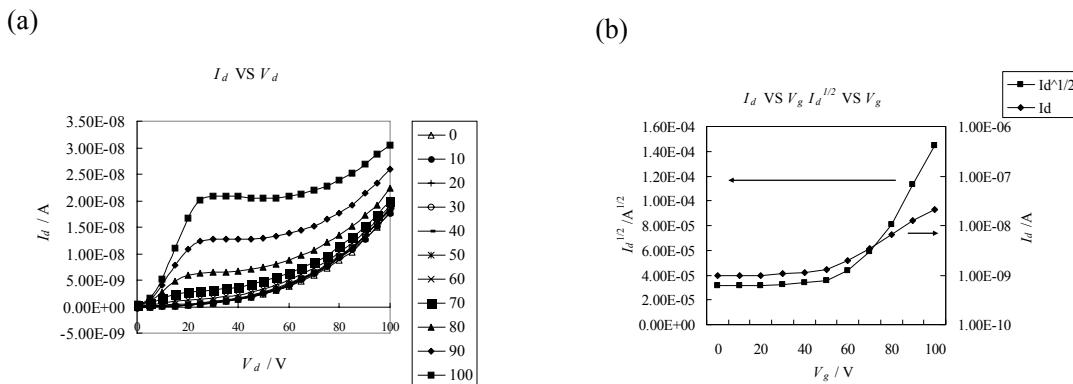


Figure S18. (a) Output characteristics of **2a** and (b) transfer characteristics of **2a** at a drain voltage of 30 V (annealed at 100 °C, Bare). The mobility calculated in the saturation regime is $1.5 \times 10^{-7} \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$ (SiO₂: 300 nm, $L/W = 25/294000$).

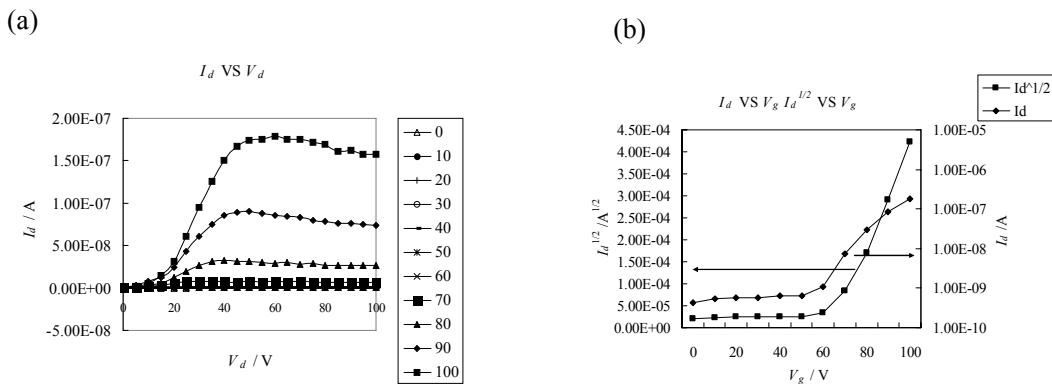


Figure S19. (a) Output characteristics of **3a** and (b) transfer characteristics of **3a** at a drain voltage of 60 V (annealed at 100 °C, Bare). The mobility calculated in the saturation regime is $2.1 \times 10^{-6} \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$ (SiO₂: 300 nm, $L/W = 25/294000$).

4. XRD patterns

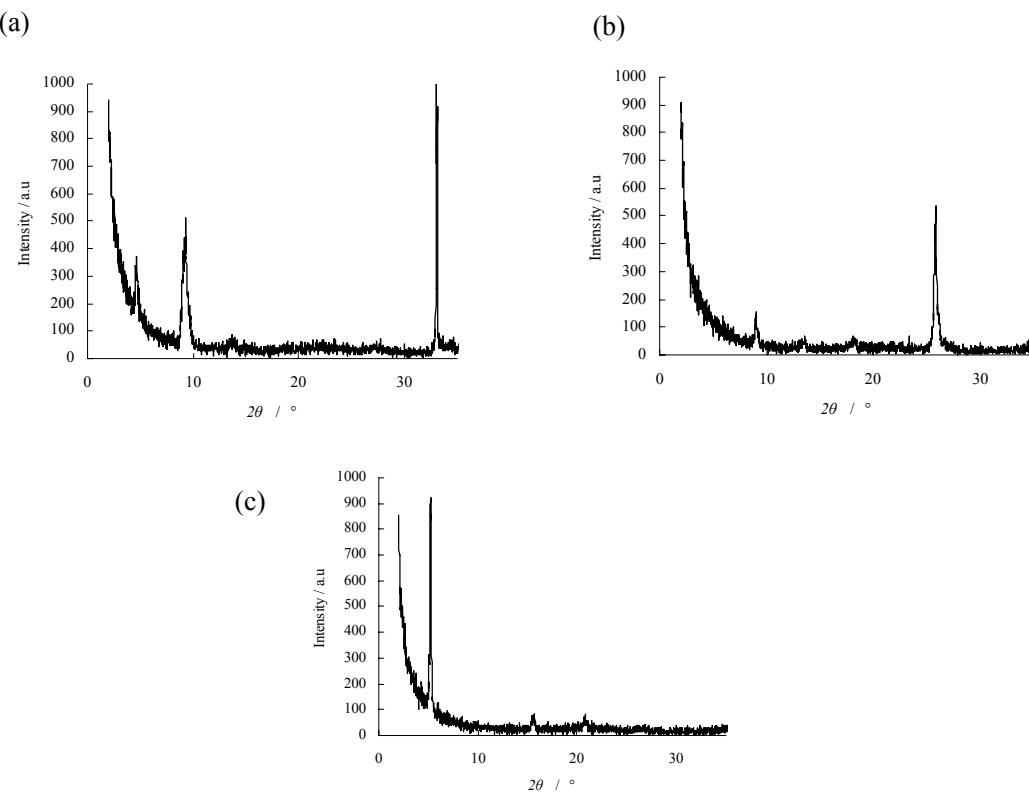


Figure S20. X-ray diffractograms of 50 nm films (a) for **1**, (b) for **4** and (c) for **5** deposited at 20 °C on untreated substrates.

Films of compound **2b**, **3b**, and **6** did not show XRD peaks.

5. AFM measurement

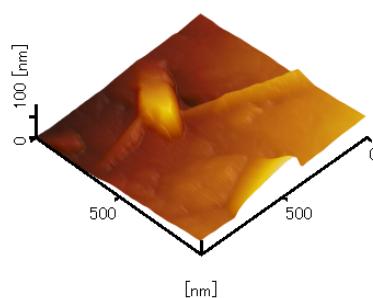


Figure S21. AFM image of a 50 nm film of compound **1** deposited at 20 °C on an untreated substrate.